



## *Future Normal in Semiconductor*

2025-02-13(목), 15:50-17:20

좌장: 추후업데이트 예정

### D. Thin Film Process Technology 분과

#### [TB3-D] Emerging Films Growth - III

<p>초청 TB3-D-1 16:50-17:05</p>	<p><b>Dimensional Scaling of Transition Metal Phosphides for Advanced Interconnect</b> Gangtae Jin Gachon University</p>
<p>TB3-D-2 16:20-16:35</p>	<p><b>The Novel Microstructure Design with Nanowire-Bundled Grain Boundaries in Thermoelectric Materials via Atomic Layer Deposition</b> Gwang Min Park<sup>1,2</sup>, Seong Keun Kim<sup>1,2</sup>, Seung-Hyub Baek<sup>2</sup>, Jin-Sang Kim<sup>2</sup>, Seunghyeok Lee<sup>2,3</sup>, Jinseok Hong<sup>4</sup>, Seokho Nahm<sup>4</sup>, Seung-Yong Lee<sup>4,5</sup> <sup>1</sup>KU-KIST Graduate School of Converging Science and Technology, Korea University, <sup>2</sup>Electronic Materials Research Center, Korea Institute of Science and Technology, <sup>3</sup>Department of Materials Science and Chemical Engineering, Hanyang University, <sup>4</sup>Division of Materials Science and Engineering, Hanyang University, <sup>5</sup>Department of Battery Engineering, Hanyang University</p>
<p>TB3-D-3 16:35-16:50</p>	<p><b>Composition-Controlled Hafnium-Based Inorganic/Organic Hybrid Dry Resist for EUV Lithography via Advanced Atomic Layer Deposition</b> Kyungryul Ha, Dong Geun Kim, Hyekyung Kim, Ji-Hoon Ahn, Woo-Hee Kim, and Tae Joo Park Department of Materials Science and Chemical Engineering, Hanyang University</p>
<p>TB3-D-4 16:50-17:05</p>	<p><b>Molecular Layer Deposition of Tin-Based Organic-Inorganic Hybrid Films as Photoresists</b> Dong Geun Kim, Kyungryul Ha, Hyekyung Kim, Woo-Hee Kim, Tae Joo Park, and Ji-Hoon Ahn Department of Materials Science and Chemical Engineering, Hanyang University</p>
<p>TB3-D-5 17:05-17:20</p>	<p><b>Interface Engineering for High Thermoelectric Performance via Atomic Layer Deposition of ZnO-TiO<sub>2</sub> Multilayers</b> Su Min Eun, Jin Kyeong Shin, Ye Jin Jeong, and Byung Joon Choi Department of Material Science and Engineering, Seoul National University of Science and Technology</p>